

**In the Claims:**

All pending claims have been reproduced below for the convenience of the Examiner.

Claims that have been changed by this amendment are indicated with an asterisk ("\*").

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\* 19. An apparatus, comprising:

a flip chip integrated circuit having flip chip bond pads with solder bumps formed thereon an active surface of the flip chip; and

B1 a substantially uniform layer of at least partially cured underfill adhesive formed on the active surface of the flip chip integrated circuit that is formed on the flip chip before the flip chip is mounted onto the substrate upon which the flip chip integrated circuit is intended to be mounted.

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20. The apparatus of claim 19, wherein the underfill adhesive includes one or more of the following components: an epoxy resin, a hardener, a catalyst initiator, a coloring dye, and an inorganic filler.

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\* 21. The apparatus of claim 19, wherein the underfill adhesive has a coefficient of B2 thermal expansion substantially similar to that of the substrate upon which the flip chip integrated circuit is intended to be mounted.

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22. The apparatus of claim 19, wherein the underfill adhesive is deposited on the active surface of the flip chip integrated circuit at a pre-cured height such that the solder bumps are at least exposed through the underfill adhesive after the partial curing.

23. The apparatus of claim 22, wherein the pre-cured height of the underfill adhesive applied to the wafer ranges from 140% to 90% of the height of the solder bumps.

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\* 24. The apparatus of claim 19, wherein the underfill adhesive layer is deposited on the active surface of the flip chip integrated circuit in wafer form before the flip chip integrated circuit is singulated from the wafer.

\* 25. The apparatus of claim 19, wherein the underfill adhesive is selected from the group comprising: epoxies, poly-imides, silicone-polyimide copolymers.

\* 26. The apparatus of claim 19, wherein the substrate has a plurality of contact pads, the contact pads configured to contact the solder bumps of the flip chip when the flip chip is mounted onto the substrate, the contact pads and the solder bumps forming joints electrically connecting the flip chip to the substrate.

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27. The apparatus of claim 26, wherein the underfill adhesive material is fully cured when the solder bumps of the flip chip and the contact pads of the substrate are reflowed.

28. The apparatus of claim 19, wherein the layer of underfill adhesive is substantially opaque thereby protecting the flip chip integrated circuit from photo induced leakage currents by blocking visible light.

29. The apparatus of claim 19, wherein the underfill adhesive has a coefficient of thermal expansion in the range of approximately  $20 \times 10^{-6}/K$  to approximately  $30 \times 10^{-6}/K$  @ 25 °C.

30. The apparatus of claim 19, wherein the underfill adhesive melts at between 120 to 140 degrees C and reacts at between 175 to 195 degrees C.

31. The apparatus of claim 19, wherein the underfill adhesive has an elastic modulus in the range of 1 to 10 GPa.

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B4 \* 32. The apparatus of claim 24, further comprising a dam around the periphery of the wafer to prevent the underfill material deposited onto the surface of the wafer from flowing off the wafer before the partial curing of the adhesive layer.

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33. The apparatus of claim 26, wherein a solder paste is provided on the contact pads of the substrate prior to mounting the flip chip.

34. The apparatus of claim 26, wherein a fluxing material is provided on the substrate prior to mounting the flip chip.

Please add the following new claims:

35. An apparatus, comprising:  
a semiconductor wafer having an active surface including a plurality of die formed thereon;  
one or more bond pads formed on the plurality of die;  
one or more solder bumps formed on the one or more bond pads respectively; and

a layer of at least partially cured underfill adhesive formed on the active surface of the wafer.

36. The apparatus of claim 35, wherein the underfill adhesive is deposited on the active surface of the wafer at a pre-cured height such that the solder bumps are at least exposed through the underfill adhesive after the partial curing.

37. The apparatus of claim 36, wherein the pre-cured height of the underfill adhesive applied to the wafer ranges from 140% to 90% of the height of the solder bumps.

38. The apparatus of claim 34, wherein the underfill adhesive is selected from the group comprising: epoxies, poly-imides, silicone-polyimide copolymers.

39. A apparatus claim 34, wherein the layer of underfill adhesive is substantially opaque.

40. The apparatus of claim 34, wherein the underfill adhesive has a coefficient of thermal expansion in the range of approximately  $20 \times 10^{-6}/K$  to approximately  $30 \times 10^{-6}/K$  @ 25 °C.

41. The apparatus of claim 34, wherein the underfill adhesive melts at between 120 to 140 degrees C and reacts at between 175 to 195 degrees C.

42. The apparatus of claim 34, wherein the underfill adhesive has an elastic modulus in the range of 1 to 10 GPa.

43. The apparatus of claim 34, further comprising a dam around the periphery of the wafer to prevent the underfill material deposited onto the active surface of the wafer from flowing off the wafer before the partial curing of the adhesive layer.